

ABSTRACT

The present disclosure provides a reaction chamber and a reaction device. The reaction chamber comprises a hollow heating member, a rotating platform, a protection plate assembly and a separator. The rotating platform is rotatably provided in an inner cavity of the hollow heating member. The rotating platform is used for bearing a wafer. The protection plate assembly is provided on two sides of the rotating platform. The separator is erected on the protection plate assembly. The separator is matched with the protection plate assembly. A reaction cavity is divided in the inner cavity, the rotating platform is surrounded by the reaction cavity, and the surface of the inner cavity is not exposed in the reaction cavity. A tray is surrounded by the reaction cavity, such that the tray is not exposed to the inner surface of the hollow heating member which is complex in structure and high in cost. A reaction gas flows through the reaction cavity and is not deposited on the surface of the hollow heating member. Only the front protection plate, the rear protection plate and the separator which are simple in structure and low in cost need to be replaced, the maintenance convenience is good, and the maintenance cost of the reaction chamber is reduced.

(To be published with Fig. 5)